

Trion Technology Sells Further Four Titan Production Platforms To A World Leader In High Brightness LED Marketplace



Clearwater, FL, USA, July 11, 2008 - Trion Technology (www.triontech.com), manufacturer of plasma etch, strip and deposition systems for critical surfaces in the semiconductor and related industries, is pleased to announce the sale of a further four of its Titan production platforms to a world leader in the high brightness LED marketplace.

The Titan is a compact fully automated vacuum cassette platform capable of batch processing of substrates from 2" through to 4" and of single wafers from 4" to 12". The Titan is available in either Reactive Ion Etch (RIE) configuration, High Density Inductive Coupled Plasma (HDICP) or Plasma Enhanced Chemical Vapor Deposition (PECVD) configuration. The small system width provides very high throughput per linear foot in the fab.

Trion has a fully equipped laboratory for process support both prior to and subsequent to purchase. For a more detailed discussion, or for sales and service representatives worldwide, please visit www.triontech.com

